Amendments to the Claims:

Please amend claim 1 as follows, cancel claims 2 and 3 without prejudice or disclaimer of the subject matter thereof and add the following new claims.

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (currently amended) A vacuum processing apparatus comprising:

a transfer unit disposed at a center thereof;

plural processing chambers, each processing chamber having a processing table for supporting an object to be processed and carrying out processing using a gas; and

a mass flow controller interposed between two of the plural processing chambers for supplying gas to the two of the plural processing chambers.

Claims 2 and 3 (canceled)

Claims 4 - 6 (canceled)

7. (new) A vacuum processing apparatus according to claim 1, wherein the two of the plural processing chambers are coupled to the transfer unit so as to be adjacent one another, and the mass flow controller is interposed between the two of the plural processing chambers which are adjacent one another.

8. (new) A vacuum processing apparatus according to claim 7, wherein the mass flow controller includes a first mass flow control unit for supplying gas to one of the two adjacent processing chambers and a second mass flow control unit for

supplying gas to another of the two adjacent processing chambers, the first and second mass flow controller units being disposed with respect to one another in a vertical direction.

9. (new) A vacuum processing apparatus according to claim 8, wherein the two adjacent processing chambers are detachably connected to the transfer unit.

10. (new) A vacuum processing apparatus comprising:

at least one processing chamber being subjected to a vacuum state for processing a wafer disposed therein, the at least one processing chamber being supplied with a processing gas to generate plasma which is utilized to process the wafer disposed therein;

wherein the at least one processing chamber includes two vacuum processing chambers disposed adjacent to one another and being detachably connected to the vacuum processing apparatus; and

plural controllers for controlling the supply of the processing gas into each of the two vacuum processing chambers, the plural controllers being disposed between the two vacuum processing chambers which are disposed adjacent one another.

11. (new) A vacuum processing apparatus according to claim 10, further comprising a transfer chamber for enabling transfer of the wafer, the two vacuum processing chambers being detachably connected to the transfer chamber so as to enable transfer of the wafer between a respective vacuum processing chamber and the transfer chamber.

12. (new) A vacuum processing chamber according to claim 11, wherein the transfer chamber has a polygonal shape in plan view, and each of the two vacuum processing chambers are disposed on respective side walls forming two adjacent sides of the polygonal shape of the transfer chamber.

13. (new) A vacuum processing apparatus according to claim 10, wherein the plural controllers are disposed adjacent one another in a vertical direction, one of the plural controllers supplying gas to one of the two vacuum processing chambers and the other of the plural controllers supplying gas to the other of the two vacuum processing chambers.

14. (new) A vacuum processing apparatus according to claim 10, wherein the plural controllers are disposed in a space between the two adjacent vacuum processing chambers.

15. (new) A vacuum processing apparatus according to claim 13, wherein the plural controllers are detachable from the vacuum processing apparatus as one unit.

16. (new) A vacuum processing apparatus according to claim 11, wherein the plural controllers are disposed adjacent one another in a vertical direction, one of the plural controllers supplying gas to one of the two vacuum processing chambers and the other of the plural controllers supplying gas to the other of the two vacuum processing chambers.

17. (new) A vacuum processing apparatus according to claim 11, wherein the plural controllers are disposed in a space between the two adjacent vacuum processing chambers.

18. (new) A vacuum processing apparatus according to claim 17, wherein the plural controllers are detachable from the vacuum processing apparatus as one unit.

19. (new) A vacuum processing apparatus according to claim 12, wherein the plural controllers are disposed adjacent one another in a vertical direction, one of the plural controllers supplying gas to one of the two vacuum processing chambers and the other of the plural controllers supplying gas to the other of the two vacuum processing chambers.

20. (new) A vacuum processing apparatus according to claim 12, wherein the plural controllers are disposed in a space between the two adjacent vacuum processing chambers.

21. (new) A vacuum processing apparatus according to claim 19, wherein the plural controllers are detachable from the vacuum processing apparatus as one unit.

22. (new) A vacuum processing apparatus according to claim 20, wherein the plural controllers are detachable from the vacuum processing apparatus as one unit.